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APJ ABDUL KALAM TECHNOLOGICAL UNIVERSITY

Third Semester B.Tech Degree Examination December 2020 (2019 Scheme)

Course Code: ECT201 **Course Name: SOLID STATE DEVICES** Max. Marks: 100 **Duration: 3 Hours** PART A Answer all questions. Each question carries 3 marks Marks With suitable examples, distinguish between elemental and compound 1 (3) semiconductors. Give their applications. 2 Draw the energy band diagrams under equilibrium for the following (3) semiconductors. i) intrinsic ii) n type iii) p type 3 Write down the current equations in a semiconductor. (3) 4 What is the significance of quasi fermi level? If there is gradient in quasi fermi (3) level, what does it indicates? 5 Draw the V-I characteristics of a P N junction diode & mark the regions of (3) operation. Write down the ideal diode equation. Draw the structure of a PNP transistor. Clearly Indicate the current components (3) on the figure. Plot the transfer characteristics of an n-channel MOSFET. Give the current (3) equation. An nMOS transistor has W/L= 4/2, gate oxide thickness 40 A°, Mobility of (3) electrons 180 cm²/Vsec. The threshold voltage is 0.4 V, relative permittivity of gate oxide ϵ_{ox} =3.9. Calculate the drain current when Vgs = 1.5 V, Vds = 1.8 V. What is channel length modulation in MOSFETs? How does it affect the output (3) characteristics of the MOSFET? 10 Explain the principle of operation and advantage of FinFET. (3) PART B Answer any one full question from each module. Each question carries 14 marks Module 1 11 a) Derive the equation for hole concentration in a semiconductor under thermal (8)

equilibrium in terms of n_i, E_f and E_i.

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b) A silicon sample doped with $2x10^{16}$ cm⁻³ of Boron atoms. ($n_i = 1.5x10^{10}$ cm⁻³ for Silicon at 300 K) Determine, i. The equilibrium electron and hole concentrations ii. Position of fermi energy level in the band gap (6) iii. Plot the energy band diagram 12 a) Plot and explain the temperature dependence of intrinsic carrier concentration (4) in semiconductors b) With suitable sketches explain the indirect recombination mechanism via (5) traps. c) An n-type Si sample with $Nd = 10^{15} \text{ cm}^{-3}$ is steadily illuminated such that g_{op} (5) = 10^{21} EHP/cm³s. If $\tau_n = \tau_p = 1$ µs for this excitation, calculate the separation in the quasi-Fermi levels, $(F_n$ - F_p). (n_i = $1.5 x 10^{10} cm^{-3}$ for Silicon at 300 K) Module 2 13 a) Explain the term mobility with respect to semiconductors. What are the (8)factors on which the mobility depends on? Explain the variation of mobility with temperature and doping. b) A potential of 100 mV is applied across a semiconductor bar, and the resulting current is 1 mA. A magnetic field of 10⁻⁴ Wb/cm² is applied perpendicular to this semiconductor bar. The hall voltage measured is -2 (6) mV. The dimensions of the bar are width = 0.1 mm, length = 5 mm and thickness = $10 \mu m$. Find i. the type of the semiconductor bar ii. the concentration and the mobility of majority carriers 14 a) Derive continuity equation for holes. (4) b) Solve the continuity equation, under steady state conditions assuming the semiconductor is long and no drift current is present. Plot the solution. (6)c) A p type semiconductor injected at one end with minority carrier electrons, under steady state conditions. Na = $10^{15}~cm^{\text{-}3}$, $\tau_n = 0.1~\mu s,~\mu_n = 700~cm^2/V$ Sec. Calculate the electron diffusion length. (4) Module 3 15 a) With the help of energy band diagrams, explain the behaviour of the contact (10)

Schottky and ohmic contacts.

between a metal and an n -type semiconductor. Clearly distinguish between

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	b) What is base width modulation? How does it affect the input and output	(4)
	characteristics of a BJT?	
16	a) Derive the equation for the built in potential of a PN junction under thermal	(7)
	equilibrium.	
	b) A PN junction, doped on one side with $10^{18} \mathrm{cm}^{-3}$ Boron atoms and the other	
	side with 10^{16} cm ⁻³ of Arsenic atoms at 300 K. ($n_i = 1.5 \times 10^{10}$ cm ⁻³ at 300 K	(3)
	and ϵ_r =11.9 for Silicon). Calculate, the built in potential.	
	c) The following parameters are given for a PNP transistor. I_{EP} = 2 mA, I_{En} =	
	0.01 mA, I_{cP} = 1.98 mA and I_{cn} = 0.001mA. Determine	
	i. The base transport factor	
	ii. The emitter injection efficiency	(4)
	iii. α and β	
	Module 4	
17	a) Draw and explain the C-V Characteristics of an Ideal MOS capacitor. Derive	(8)
	the expression for threshold voltage.	
	b) Draw the energy band diagrams, of an ideal MOS capacitor under	
	equilibrium, and strong inversion conditions.	(6)
18	a) Draw the structure of n channel MOSFET. Derive the expression for drain	(10)
	current of a MOSFET in the two regions of operation. What are the assumptions	
	made in deriving the expression?	
	b) What is meant by body effect in MOSFET? How does it affect the threshold	(4)
	voltage of the MOSFET?	
	Module 5	
19	a) What is meant by scaling in MOSFETs? Explain the challenges in device	(7)
	scaling?	
	b) Explain the concept of constant voltage scaling and its limitations.	(7)
20	a) What is meant by DIBL in MOSFETs? How does it affect the threshold	(7)
	voltage of a MOSFET?	
	b) Explain the concepts of velocity saturation and hot carrier effects in a	(7)
	MOSFET.	
